

Serial No. 09/880.465

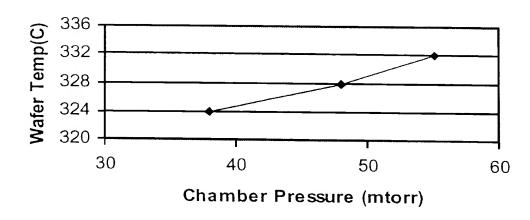


FIG. 1



Atomic Concentration (%)

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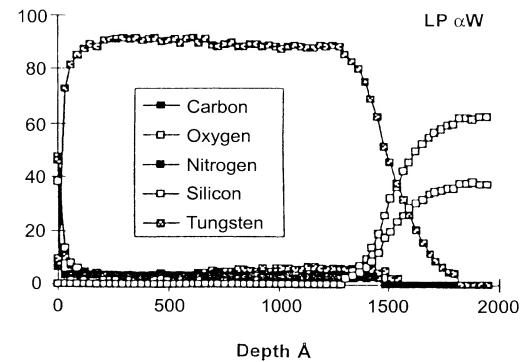
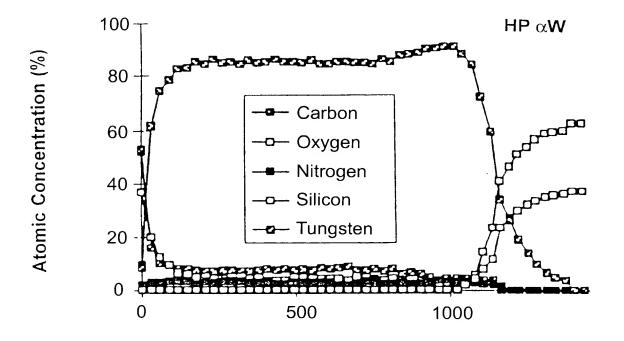


FIG. 2A



Depth Å



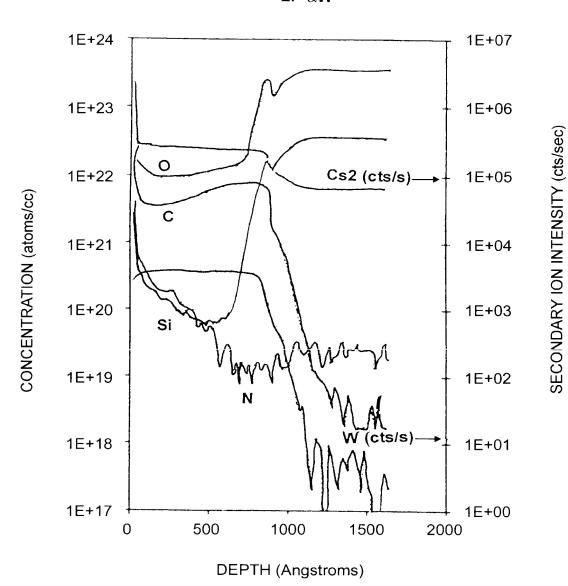


FIG. 3A



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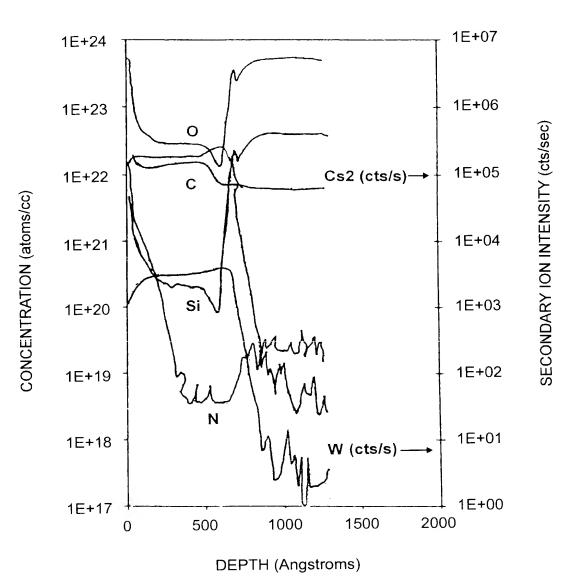


FIG. 3B



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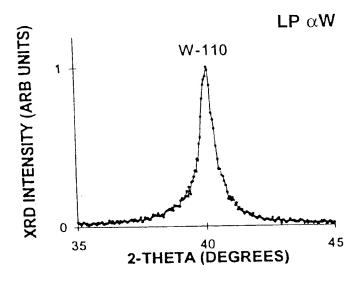


FIG. 4A

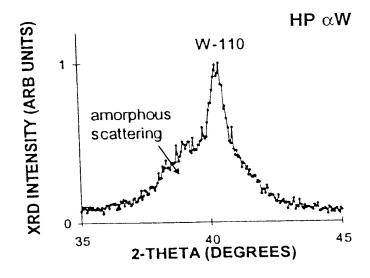


FIG. 4B



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## $\text{LP } \alpha \text{W}$

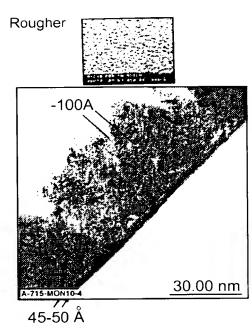


FIG. 5A

## HP $\alpha$ W

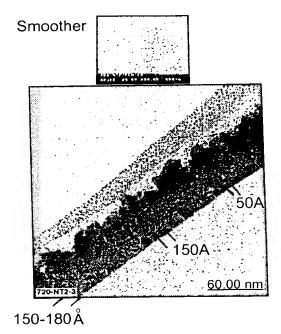


FIG. 5B